XJP-405

XJP-405 industrial microscope is equipped with a large moving range mechanical stage, Epi-illuminator, long working distance bright and dark field Infinite Plan objectives, wide field eyepiece with clear images and good contrast. It is developed and aimed at the semiconductor industry, wafer manufacturing, electronic information industry, metallurgical industry, and used as a high-grade industrial microscope. Bright ＆ Dark-field observation, EPI-polarizing, and DIC observation can proceed. It is widely used in Factories, Research institution and college and Universities to identify and analyze Wafer, FPD, Circuit substrate, Precision molds.

Specification	
Viewing Head	Compensation Free Trinocular Head, Inclined 30°（50mm-75mm）
Eyepiece	WF10×/25mm
	WF10×/20mm,crosshair with reticule 0.1mm
Nosepiece	Quintuple Nosepiece with DIC Jack
Objective	Long working distance bright and dark field Infinite Plan objectives: 5 ×/0.1B.D/W.D.29.4mm 10×/0.25B.D/W.D.16mm 20×/0.40B.D/W.D.10.6mm 40 ×/0.60B.D/W.D.5.4mm
Stage	Double layer mechanical stage
	Stage Size: 350mm×310mm
	Moving Range:250mm×250mm
Filter	Flashboard type filters(green,blue,neutral)
Focusing	Coaxial coarse ＆fine focusing adjustment With rack and pinion mechanism Fine focusing scale value 0.002mm
Light Source	Epi-illumination: With aperture iris diaphragm and field iris Diaphragm, Halogen Bulb 12V/100W, AC85V-230V, Brightness Adjustable
Polarizing Device	Analyzer rotatable 360,°Polariaer＆Analyzer can be moved in/out of the optical path
Checking Tool	0.01mm Micrometer
Optional Accessory	Eyepiece: WF15×/17mm、WF20×/12.5mm
	1.3Mega、2.0 Mega、3.0 Mega、5.0 Megapixels CMOS Digital camera eyepiece
	Long working distance bright and dark field Infinite Plan objectives: 50 ×/0.55B.D/W.D.5.1mm、 80×/0.75B.D/W.D.4mm、100×/0.80B.D/W.D.3mm
	Two-dimensional measurement software
	Professional metallurgical image analysis software
	DIC（10×、20×、40×、100×）
	Photography attachment and CCD Adapter 0.5×、0.57×、0.75×
	Planish tool
	CCD Camera,colour 1/3″High resolution 520 TV lines

Characteristics and description

1.Adopt US High-1. 1.Adopt UIS High-resolution, Long working distance, and infinity light path correcting system objective imaging technology
2.Extending the multiplexing technology of objective, compatible infinity objective with all the observation methods. including brigh& dark field observation, polarization and also provide with high clear and sharp image in each observation method.
3.Aspherical surface Kohler illumination, increasing the viewing brightness.
4.WF10 X（Φ25）super wide field Eyepiece, long working distance metallurgical objective with bright and dark field
5.The Nosepiece can be equipped with detachable DIC differential interference device.